

REMARKS/ARGUMENTS

The applicants' attorneys appreciate the Examiner's thorough search and remarks.

Responsive to paragraph 3 of the Office Action, claim 1 has been amended to call for an oxide body instead of a low temperature oxide body and claim 7 has been canceled.

Reconsideration is requested.

Claim 1 has been rejected as anticipated by Hirohiko, JP 2000-101074. Reconsideration is requested.

Hirohiko teaches forming an N-type well region 33, par. [0018], line 12, and an N-type base area 29, par. [0020], line 16. Because the device shown by Hirohiko is a trench type switch and because well region 33 and base region 29 are of the same conductivity type, it can be concluded that well region 33 and the epitaxial body in which it is formed are of different conductivity types.

A termination trench 76 is formed inside N-type well region 33 and includes a bottom that is adjacent an N-type region, which is part of well region 33, and a sidewall that is adjacent an N-type region, which is also a part of well region 33. Thus, the sidewall and the bottom of the termination trench in Hirohiko are adjacent well region 33, which is of a conductivity type opposite the drift region of the device.

On the other hand, claim 1 calls for the sidewall of the termination trench to be adjacent the channel region and the bottom of the termination to be adjacent a region of a conductivity type opposite the conductivity type of the channel region (i.e. a region of first conductivity type). Thus, claim 1 should not be deemed anticipated by Hirohiko. Reconsideration is requested.

In addition, in Hirohiko, the gate trenches 75 and the termination trench 76 extend to the same depth as they are formed in the same step.

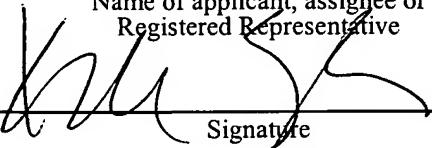
On the other hand, in claim 11, a device according to the present invention includes trenches and a termination trench of different depths, and claim 12 calls for the trenches to be deeper than the termination trench. It is respectfully submitted that claims 11 and 12 should not be deemed anticipated by Hirohiko.

Each of the remaining claims depends from claim 1, and, therefore, includes the limitations thereof as well as additional limitations which in combination with those of claim 1 are not shown or suggested by the art of record. Reconsideration is requested.

The application is believed to be in condition for allowance. Such action is earnestly solicited.

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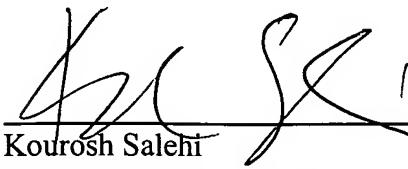
Name of applicant, assignee or
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Signature

August 22, 2008
Date of Signature

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Respectfully submitted,



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